

In re the Application of: IMAI, Genji

Group Art Unit: 1752

Serial No.: 09/976,279

Examiner: Yvette C. Thornton

Filed: October 15, 2001

P.T.O. Confirmation No.: 1120

FOR: NEGATIVE PHOTOSENSITIVE RESIN COMPOSITION, NEGATIVE PHOTOSENSITIVE DRY FILM AND METHOD OF FORMING PATTERN

AMENDMENT UNDER 37 CFR §1.111

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

September 22, 2004

Sir:

In response to the Office Action dated March 25, 2004, extended to September 25, 2004, by a three-month Petition for Extension of Time, please amend the above-identified application as follows:

Amendments to the Claims are reflected in the listing of claims which begins on page 2 of this paper.

Remarks/Arguments begin on page 5 of this paper.